

**IN THE SPECIFICATION:**

Page 1, before the first paragraph, insert the heading:

--Field and Background of the Invention--

Page 4, before the first paragraph, insert the heading:

--Summary of the Invention--

Page 13, amend the paragraph beginning on line 13 to read:

--Further preferred embodiments of the vacuum treatment installation according to

C 3 the invention as well as of the ultrahigh vacuum CVD reactor according to the invention are apparent to a person skilled in the art on the basis of the following description of examples and are in particular specified in claims 23 to 45.--

Page 13, before the paragraph beginning on line 23, insert the heading:

--Brief Description of the Drawings--

Page 15, before the paragraph beginning on line 1, insert the heading:

--Description of the Preferred Embodiments--

Page 29, amended the paragraph beginning on line 5 to read:

--With the methods according to the invention, the vacuum treatment installation

C 4 according to the invention or the UHV-CVD reactor according to the invention, structural members are produced by [[eliminate return]] deposition of atom monolayers (atomic layer deposition) or by deposition of epitactic layers or by coating of deep-profiled surfaces, such

as surfaces with so-called deep trenches.--

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